

**AMENDMENT TO SPECIFICATION**

**IN THE SPECIFICATION:**

A marked-up copy of the changes to selected paragraph(s) is provided below.  
Please enter these changes to the specification in the record.

Please replace Paragraph [0017] with the following:

[0017] The resist is typically an organic resist which is usually spin-coated onto the opaque material ~~42~~14 in preparation for photolithographic imaging. An example of an organic resist suitable to be used with embodiments of the invention include a chemical amplified resist (CAR). After the structure 10 is formed, it is then exposed 18 using a photolithographic imaging device. Typically the photolithographic imaging device is an E-beam writer. However, other imaging devices may be used in accordance with the principles of the invention.